

Electronic Devices

Lecture 7

20-08-2018

Acceptor Doping - Electron and Hole Densities

- Virtually all acceptors are ionized at room temperature (**complete ionization**), and N_A is normally much larger than n_i - the valence band hole density p is essentially just the density of acceptors, with n given by the mass action law

$$p = N_A \quad n = \frac{n_i^2}{p} = \frac{n_i^2}{N_A}$$

- Since $p \gg n$ for acceptor doping, the material is termed **p-type**, holes are called the **majority carriers** and electrons the **minority carriers**
 - Acceptor doping allows direct control of p
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A sample of silicon is doped with $4 \times 10^{16} / \text{cm}^3$ of Gallium (Ga), a group III atom. What are the concentrations of electrons and holes?

- As a group III atom Gallium functions as an acceptor, so the doped material is therefore *p*-type. The density of holes is essentially equal to the density of acceptors, so

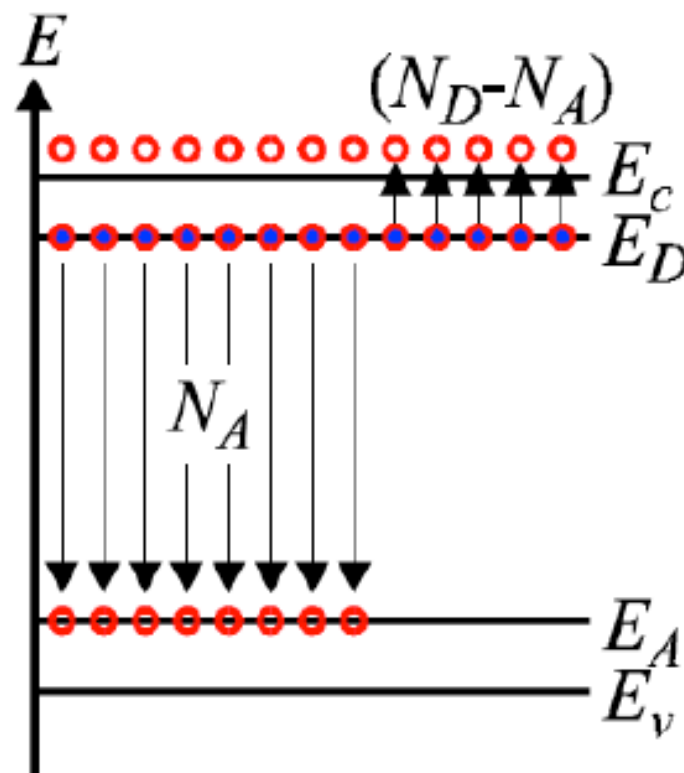
$$p = N_A = 4 \times 10^{16} / \text{cm}^3$$

- The density of electrons is given by the mass-action law as

$$n = \frac{n_i^2}{p} = \frac{n_i^2}{N_A} = \frac{(1.45 \times 10^{10})^2}{4 \times 10^{16}} = 5.3 \times 10^3 / \text{cm}^3$$

Compensated Doping

- In practice there are many cases where both donor and acceptor dopants are present in a region of material
- This is referred to as **compensated** doping
- First order model is to consider that the larger doping determines the type, and the net doping determines n or p
- Example to the right is for the case $N_D > N_A$



A sample of silicon is doped with $3 \times 10^{16} / \text{cm}^3$ of Phosphorous (P, group V) and $6 \times 10^{16} / \text{cm}^3$ of Boron (B, group III). What type is the material, what are the concentrations of electrons and holes, and which are the majority and minority carriers?

- For this example, the density of acceptors (B) is greater than the density of donors (P). The material is \therefore *p*-type.
- The hole density is determined by the net acceptor doping

$$p = N_A - N_D = 6 \times 10^{16} - 3 \times 10^{16} = 3 \times 10^{16} / \text{cm}^3$$

- The density of electrons is given by the mass-action law as

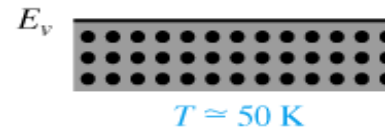
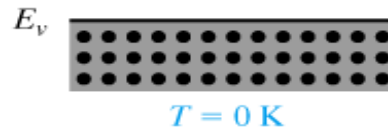
$$n = \frac{n_i^2}{p} = \frac{n_i^2}{N_A - N_D} = \frac{(1.45 \times 10^{10})^2}{3 \times 10^{16}} \approx 7 \times 10^3 / \text{cm}^3$$

- Since the material is *p*-type, holes are the majority carriers and electrons are the minority carriers

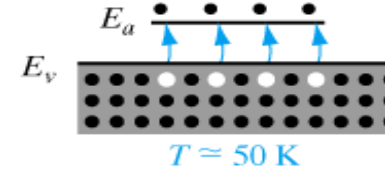
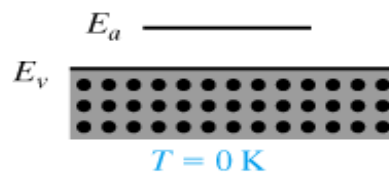
Energy Band Model vs. Covalent Bond Model



(a)



(b)



What are the majority carriers and minority carriers in Semiconductors ?

n-type semiconductor

Majority carrier-n

Minority carrier-p

$$n_o \simeq N_D$$

$$p_o \simeq \frac{n_i^2}{N_D}$$

p-type semiconductor

Majority carrier-p

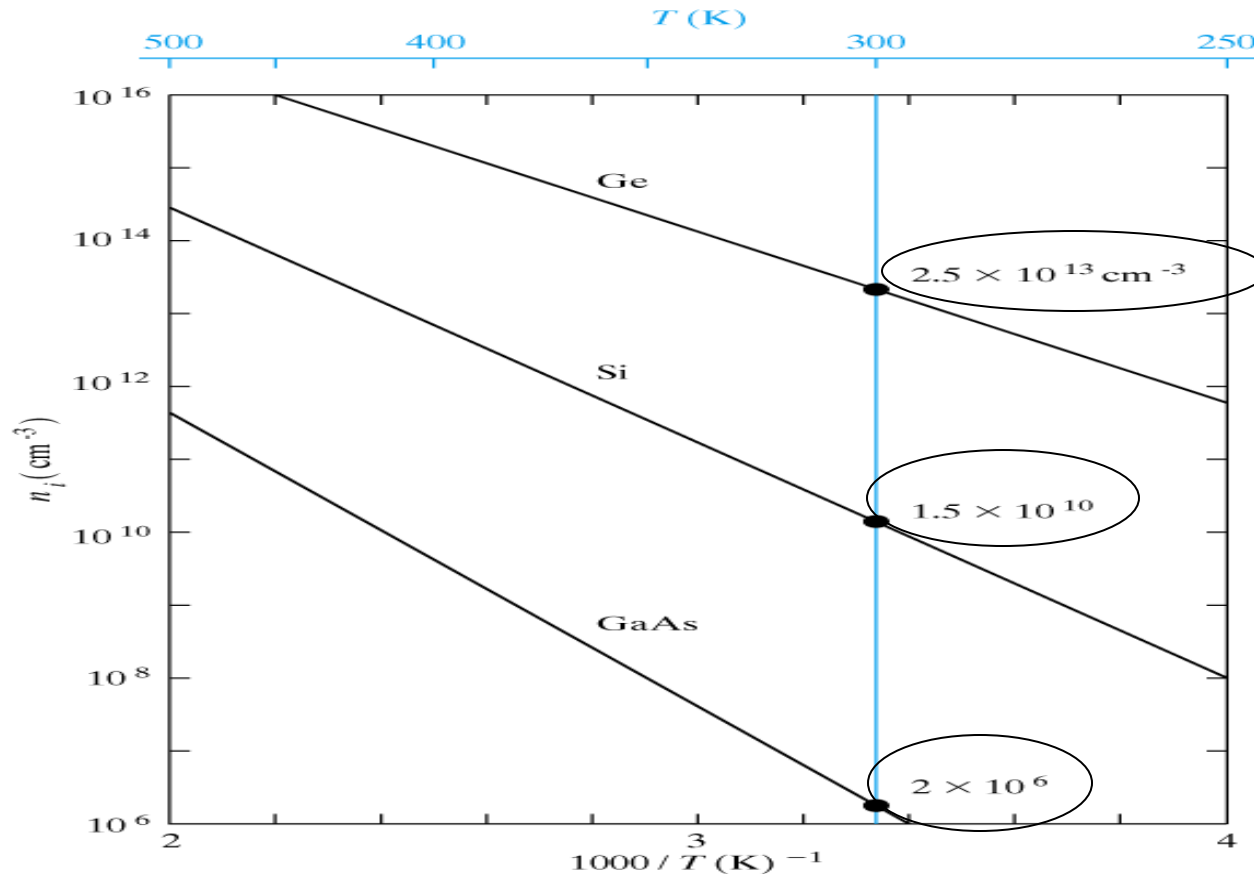
Minority carrier-n

$$p_o \simeq N_A$$

$$n_o \simeq \frac{n_i^2}{N_A}$$

In Si the intrinsic carrier conc. is $1.5 \times 10^{10}/\text{cm}^3$.
With a donor conc. Of $10^{15}/\text{cm}^3$ the conductivity can be increased by 5 orders of magnitude.

Temperature dependence of carrier concentrations



Intrinsic carrier concentration for Ge, Si, and GaAs as a function of inverse temperature. The room temperature values are marked for reference.

Compensation and space charge neutrality in an n-type semiconductor

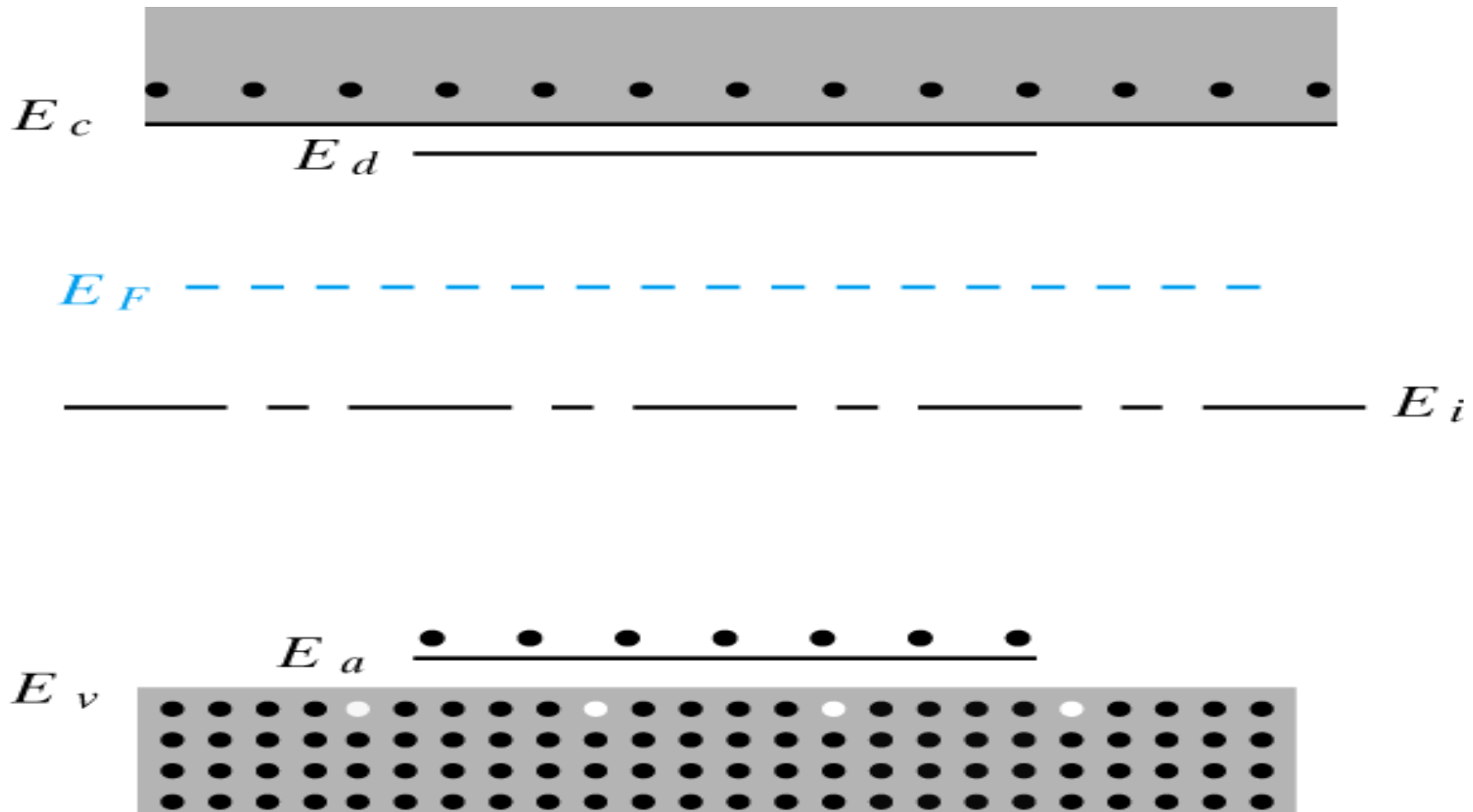
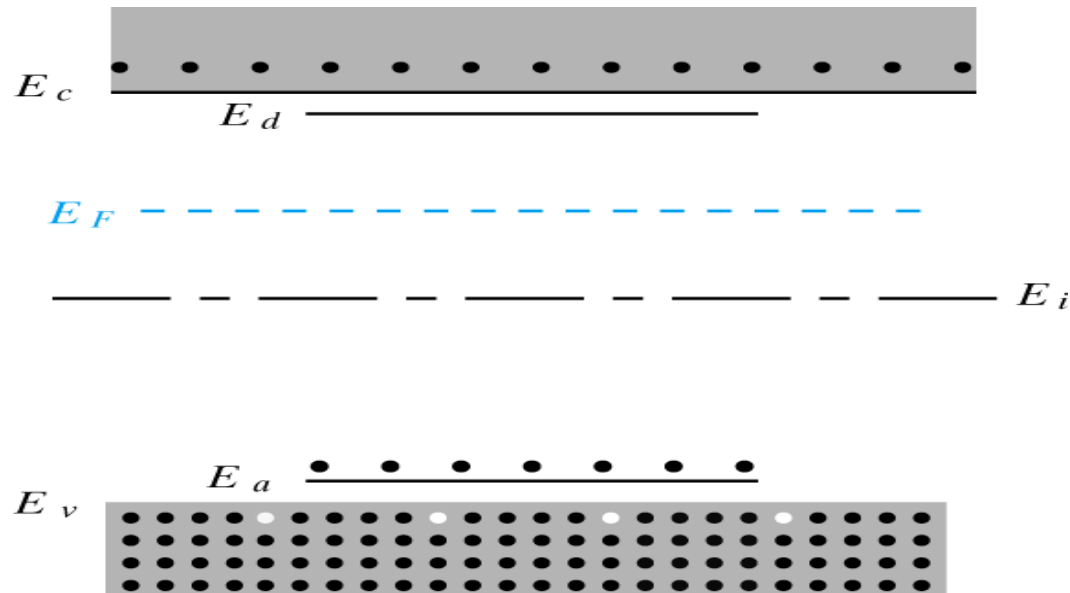


Figure 3—19

Compensation in an **n-type** semiconductor ($N_d > N_a$).



$$n_o = n_i = p_o$$

$$p_o + N_d^+ = n_o + N_a^-$$

$n_o \rightarrow$ electrons

$p_o \rightarrow$ holes

$N_d^+ \rightarrow$ donor ions

$N_a^- \rightarrow$ acceptor ions

$$p = \frac{n_i^2}{n}$$

$$N_d + p = N_a + n$$

$$n - \frac{n_i^2}{n} = N_d - N_a$$

$$\text{or } n = \frac{N_d - N_a}{2} + \left[\left(\frac{N_d - N_a}{2} \right)^2 + n_i^2 \right]^{1/2}$$

$$\text{If } N_d > N_a \text{ then } n \approx (N_d - N_a) \text{ and } p = \frac{n_i^2}{n} = \frac{n_i^2}{(N_d - N_a)}$$